

Figure 1 (left). GPC measured as a function of deposition temperature with inset GPC plot.
 Figure 2 (right). NiO thickness-per-cycle (TPC) measured as a function of precursor pulse length at a deposition temperature of 200°C.

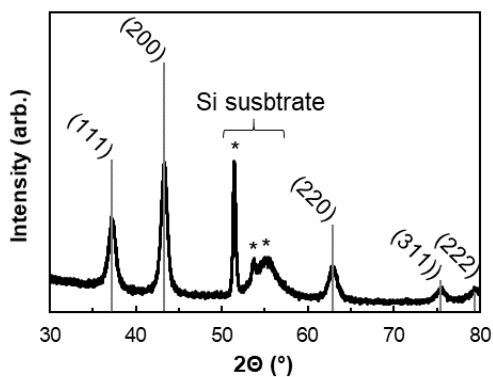


Figure 3. GIXRD spectra for an ~18 nm thick NiO film deposited at 200 °C, with indicated peaks attributed to cubic NiO. Vertical lines indicate reference intensities for NiO powder from PDF card #00-047-1049.

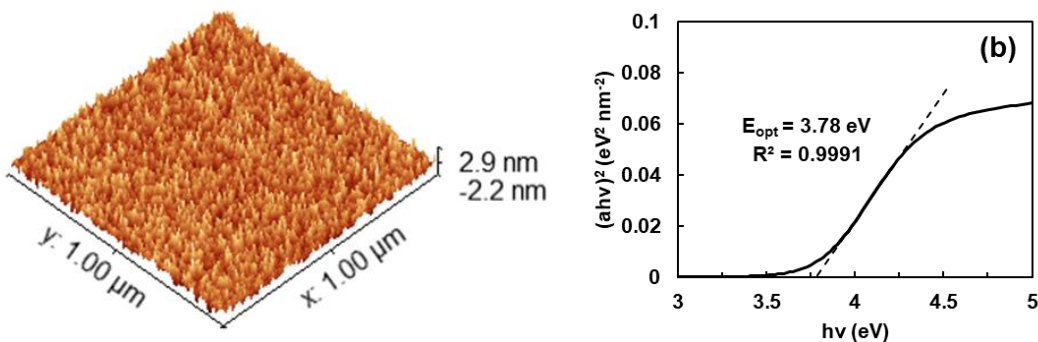


Figure 4 (left). 3D AFM micrograph of an ~18 nm thick NiO film deposited at 200 °C.

Figure 5 (right). Tauc-plot of $(ahv)^2$ versus hv with estimated band-gap indicated for a ~30 nm thick NiO film deposited at 200 °C.